Deposition Equipment for Laser Coatings on Small and Large Substrates

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Innovations for a better world.



Outline

- Motivation
- Deposition system for laser coatings
 - Plasma assisted evaporation systems
 - > Plasma assisted magnetron sputtering systems
 - ➤ Ion beam sputtering systems
- ➤ Conclusion

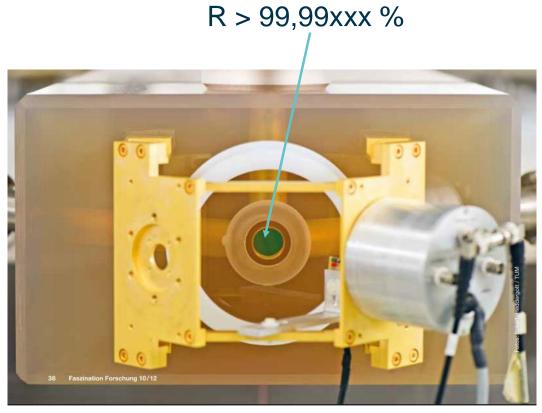






Ring laser gyroscope for exact navigation





Geodätisches Observatorium Wettzell www.fs.wettzell.de



Plasma assisted evaporation systems

- Single precision dome
- Planetary system for large optics
- Ceramic front heater
- LION 300 plasma source
- EB-evaporator HPE12/10
- Optical monitoring OMS 5100
- Substrate size up to 1000mm



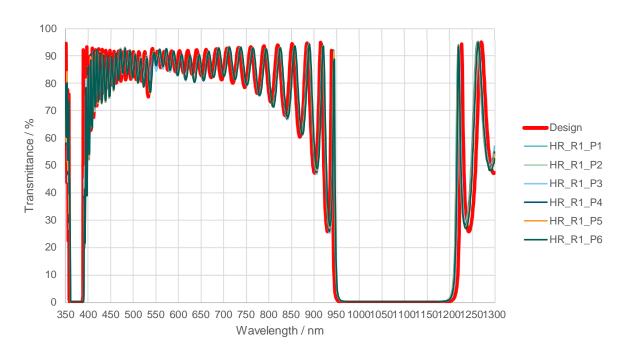


Process results HR mirror @1064nm

- Excellent uniformity
- Total loss @ 1064nm 70ppm
- R > 99,99%



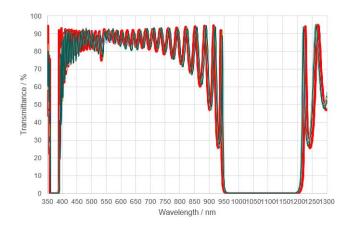
SYRUSpro 1350 - LION 300 (Dome): HR @ 1064nm on D263 (HL^17) H with Ta2O5 & SiO2: Run 1





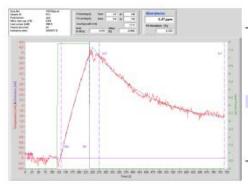
Process results HR mirror @1064nm

- Excellent uniformity
- Absorption@ 1064nm ~ 5ppm
- R > 99,99%



PH/LK/LZH 15952 -Bühler-1064nm .pdf 2020-08-05

2.2 Sample P2.3



Geometry (d x th) 25.4x1 mm Wavelength 1064 nm Substrate material FS Sample mass 1.13 g Spec. heat capacity 0.772 J/gK Absorptance (expon.) 5.5 ppm Data file 150720ab.cal Power 7.88 W NTC - Position 7 mm Calibration Factor

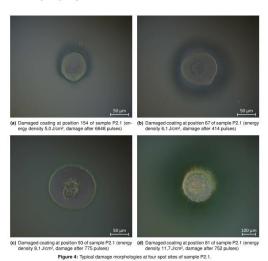
ELZH



Process results HR Mirror @1064nm

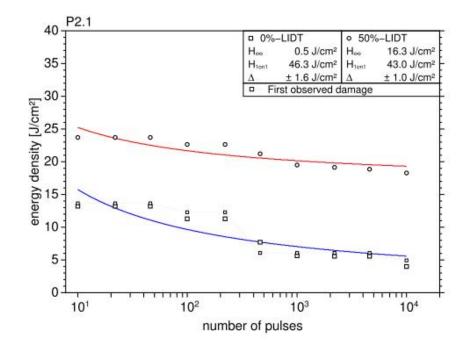
- LIDT 8ns pulse
- 10 30 J/cm²
- R > 99,99%

2.1.3 Damage Morphologies



Manufacturer: Bühler Sample type: HR 1064 nm

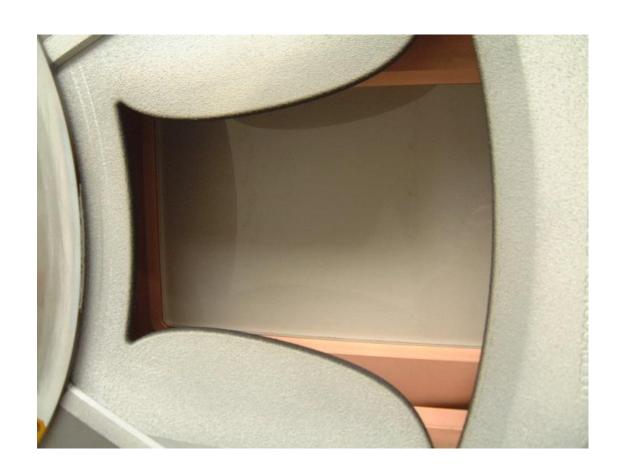
2.1.1 Characteristic Damage Plot





Plasma assisted reactive magnetron sputtering

- Fast rotating turntable
- 3 Magnetron sputter sources
- RF plasma source
- Optical monitoring OMS 5100
- RF-SiO2 target option
- Recommended substrate size for laser application up to 100mm





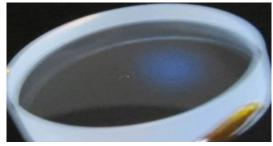
Laser coatings by RF Sputtering - HR Mirror @1064nm

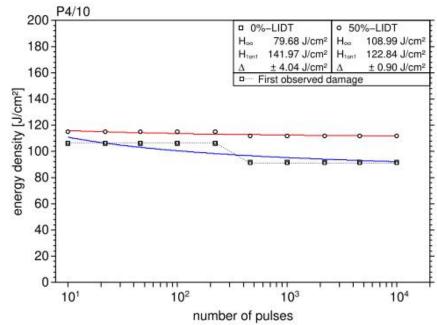
| | Laser Mirror @1064 nm |
|------------------|-----------------------------------|
| Design | HL^18L |
| Coating | SiO2 (RF) /HfO2 (MF) or Ta2O5(MF) |
| Substrate | Super polished fused silca |
| Reflection | ~ 99.996% |
| Total loss (CRD) | 15 - 40 ppm |
| Absorption | ~ 5 ppm |

2.3 Sample 191024-01 P4/10

Manufacturer: Bühler Sample type: HR 1064 nm

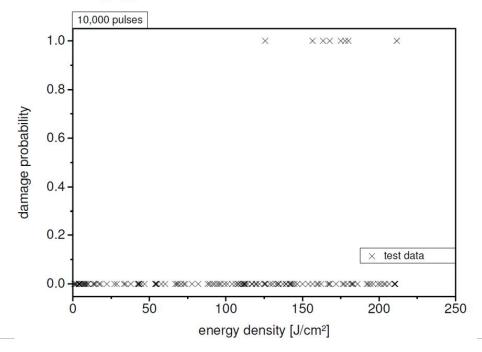
2.3.1 Characteristic Damage Plot



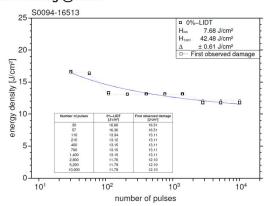


Laser coatings by RF Sputtering - High LIDT

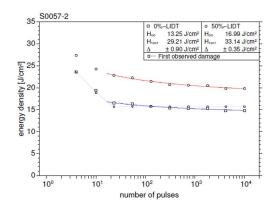
LIDT Messung @1064nm



LIDT Messung @266nm



LIDT Messung @355nm





Ion Beam Sputtering systems

- Single precision flat palette or planetary substrate carrier
- Moveable multi-target tower
- RF- Ar sputter source
- RF -O₂ assist source
- Optical monitoring OMS 5100
- Substrate size up to 600mm



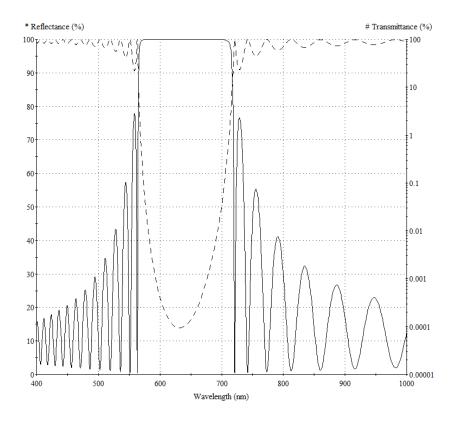


Low Loss Mirrors Refectance / Transmittance @ 633nm

- Material SiO₂ / Ta₂O₅
- Design (HL)^20 L
- Reflectance > 99.998 %@
- Transmittance loss ~ 1 ppm



LaserMirror: Transmittance





Low Loss Mirrors Absorption loss @ 532nm

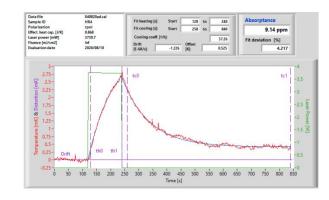
- Material SiO₂ / Ta₂O₅
- Design (HL)^20 L
- Absorption Loss ~ 9 ppm





Absorptance measurement of optical laser components according to ISO 11551:2019 at 532 nm

2.2.4 Sample HR4

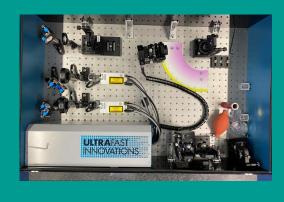


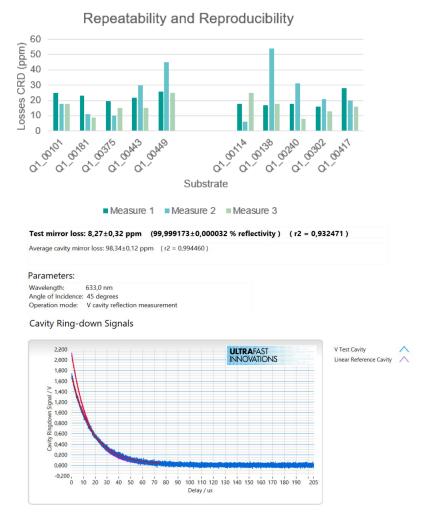
| Geometry (d x th) | 25.4x1 mm |
|----------------------|--------------|
| Wavelength | 532 nm |
| Substrate material | FS |
| Sample mass | 1.06 g |
| Spec. heat capacity | 0.772 J/gK |
| Absorptance (expon.) | 9.2 ppm |
| Data file | 040820ad.cal |
| NTC - Position | 7 mm |
| Calibration Factor | 1 |
| | |



Low Loss Mirrors Total loss @ 633nm by CRD

- Material SiO₂ / Ta₂O₅
- Design (HL)^20 L
- Total Loss < 20ppm



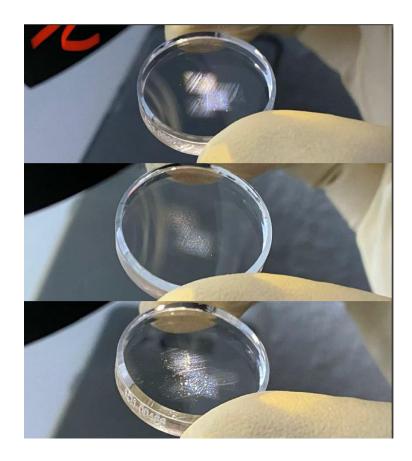




Conclusion

- Standard deposition systems for laser coatings are available for substrate sizes up to 1000mm
- To minimize the scattering losses an energetic deposition process is necessary that keeps the absorption loss low
- Measurement below 20ppm total loss is a challenge
- For high reflecting laser mirror coating excellent surface quality is essential







Thank you for your attention!



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